This listing of claims will replace all prior versions, and listings of claims in the application:

## **Listing of Claims:**

1-12 (canceled)

- 1 13. (Original) A semiconductor processing apparatus comprising:
- 2 a current source;

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current to a semiconductor device on a wafer under a predetermined ambient
temperature, the microprobe also configured to capture data concerning performance
characteristics of the semiconductor device during the application of the scan current
thereto, wherein the scan current is higher than the normal operating current of the
semiconductor devices and the predetermined ambient temperature is higher than the

a microprobe coupled to the current source, the microprobe configured to apply a scan

a processing module coupled to the microprobe, the processing module configured to receive the data captured by the microprobe and to determine whether the

normal operating temperature of the semiconductor devices; and

- semiconductor device is prone to infant mortality based on the data.
  - 14. (Original) The apparatus as recited in Claim 13, wherein the semiconductor device is a vertical cavity surface emitting laser (VCSEL) device.

- 1 15. (Original) The apparatus as recited in Claim 13, wherein the microprobe is further
  2 configured to repeatedly apply the scan current to the semiconductor device and
  3 capture the data concerning performance characteristics of the semiconductor device
  4 during each application of the scan current for a predetermined number of times, and
  5 wherein the processing module is configured to determine whether the
  6 semiconductor device is prone to infant mortality based on a comparison of the data
  7 received for said repeated applications of the scan current.
- 1 16. (Original) The apparatus as recited in Claim 13, which is configured to process a 2 plurality of said semiconductor device on the wafer.
- 1 17. (Original) The apparatus as recited in Claim 16, which is further configured to process 2 said plurality of said semiconductor device one at a time in serial fashion.
- 18. (Original) The apparatus as recited in Claim 16, which is further configured to process a
  2 subset of said plurality of said semiconductor device simultaneously, wherein said
  3 subset includes more than one but not all of said plurality of said semiconductor
  4 device on the wafer.
- 1 19. (Original) The apparatus as recited in Claim 13, wherein the microprobe is further
  2 configured to apply the scan current to the semiconductor device for as long as 20
  3 milliseconds (ms).

- 20. (Original) The apparatus as recited in Claim 13, wherein the microprobe is further configured to apply the scan current of substantially higher than 20 milliamperes (mA) to the semiconductor device.
- 21. (Original) The apparatus as recited in Claim 13, wherein the microprobe is further configured to apply the scan current of as high as 50 milliamperes (mA) to the semiconductor device.
- 22. (Original) The apparatus as recited in Claim 13, wherein the microprobe is further
   configured to apply the scan current to the semiconductor device using a current
   sweeping mode.
- 1 23. (Original) The apparatus as recited in Claim 13, wherein the microprobe is further
  2 configured to apply the scan current to the semiconductor device using a current
  3 pulsing mode.
- 1 24. (Original) A system for burning-in semiconductor devices, comprising:
- 2 a processor; and
- a mechanical module coupled to and controlled by the processor, wherein the
  mechanical module is configured to (1) apply a scan current to the semiconductor
  devices on a wafer; (2) capture data concerning performance characteristics of the
  semiconductor devices during the application of the scan current thereto, wherein the
  scan current is higher than the normal operating current of the semiconductor

8	devices; and wherein the processor is configured to receive the data captured by the
9	mechanical module for determining whether the semiconductor device is prone to
10	infant mortality.

- 25. (Original) The system as recited in Claim 24, which is configured to process vertical cavity surface emitting laser (VCSEL) devices.
- 26. (Original) The system as recited in Claim 24, wherein the mechanical module is further configured to repeatedly apply the scan current to the semiconductor devices and capture the data concerning performance characteristics of the semiconductor devices during each application of the scan current for a predetermined number of times, and wherein the processor is further configured to determine whether the semiconductor device is prone to infant mortality based on a comparison of the data received for said repeated applications of the scan current.
- 1 27. (Original) The system as recited in Claim 24, which is configured to process the semiconductor devices one at a time in serial fashion.
- 28. (Original) The system as recited in Claim 24, which is configured to process a subset of the semiconductor devices simultaneously, wherein said subset includes more than one but not all of the semiconductor devices on the wafer.

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1	29. (Original) The system as recited in Claim 24, wherein the mechanical module is further
2	configured to apply the scan current to the semiconductor devices for as long as 20
3	milliseconds (ms).
1	30. (Original) The system as recited in Claim 24, wherein the mechanical module is further
2	configured to apply the scan current of as high as 50 milliamperes (mA) to the
3	semiconductor devices.
1	31. (Original) The system as recited in Claim 24, wherein the mechanical module is further
2	configured to apply the scan current to the semiconductor devices in a current
3	sweeping mode.
1	32. (Original) The system as recited in Claim 24, wherein the mechanical module is further
2	configured to apply the scan current to the semiconductor devices in a current
3	pulsing mode.
	33-42 (canceled).